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(54) Title: LOW TOXICITY SOLVENT SYSTEM FOR POLYAMIDEIMIDE RESINS AND SOLVENT SYSTEM MANUFACTURE

(57) Abstract: Disclosed is a low toxicity aprotic alkyl amide solvent system used for the manufacture and application of polyamideimide resins, and an efficient method for manufacturing the polyamideimide resins in a solvent system in a single reaction with distillation which allows recycling of intermediate streams. The solvent system can be used for either the manufacture or the dissolution of polyamideimide resins.

